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| Application Number     |                |
| Filing Date            |                |
| First Named Inventor   | Masood Murtuza |
| Art Unit               |                |
| Examiner Name          |                |
| Attorney Docket Number | TI-35639       |

## U. S. PATENT DOCUMENTS

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## FOREIGN PATENT DOCUMENTS

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**Examiner  
Signature**

Walter A. Baryantsev

Date  
Considered

08 | 05 | 2005

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| Art Unit               | Unknown        |
| Examiner Name          | Unknown        |
| Attorney Docket Number | TI-35639       |

Sheet 2

of 2

**NON PATENT LITERATURE DOCUMENTS**

| Examiner Initials* | Cite No. <sup>1</sup> | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.                 | T <sup>2</sup> |
|--------------------|-----------------------|---|----------------|
| MAB                |                       | K. BUCHANAN, et al., "Challenges Associated with the Integration of Nano-Porous Ultra Low k CVD Films", SEMI Technical Symposium, p. 1-2, 2002  |                |
| MAB                |                       | L. PETERS, "Removing Barriers to Low-k Dielectric Adoption", <a href="http://www.reed-electronics.com/semiconductor/index.asp?layout=articlePring&amp;...">http://www.reed-electronics.com/semiconductor/index.asp?layout=articlePring&amp;...</a> , Last Viewed 8/26/03, p.1-6 |                |
| MAB                |                       | International SeMaTech, "Benchmarking Ultra Low-K Materials: Nanoglass Shows Promise", <a href="http://www.sematech.org/public/news/stories/nanoglass.com">http://www.sematech.org/public/news/stories/nanoglass.com</a> , Last Viewed 8/26/03, p. 1-2                          |                |
| MAB                |                       | "Axcelis, Dow Coming Develop Porous Ultra-Low-K Process", <a href="http://www.reed.electronics.com/electronicnews/index.asp?layout=articlePrint&amp;...">http://www.reed.electronics.com/electronicnews/index.asp?layout=articlePrint&amp;...</a> , Last Viewed 8/26/03, p. 1   |                |
| MAB                |                       | "Nanoporous Ultra-Low Dielectric Constant Materials", <a href="http://www.ncnr.nist.gov/programs/reflectometry/highlights/nano/">http://www.ncnr.nist.gov/programs/reflectometry/highlights/nano/</a> , Last Viewed 8/26/03, p. 1-3   |                |
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| Examiner Signature | <i>Masood Murtuza</i> | Date Considered | 08/05/2005 |
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